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EDITOR-IN-CHIEF Michael Pfeffer, Weingarten, Germany, University of Applied Sciences Ravensburg-Weingarten, Germany, Hochschule Ravensburg-Weingarten, Doggenriedstrasse, Postfach 1261, 88241 Weingarten, Germany, Tel.: +49 (0)751 501 9539, Fax: +49 (0)751 501 9874, Email: michael.pfeffer@hs-weingarten.de

MANAGING EDITOR Holger Kleessen, Berlin, Germany, Email: contact@advanced-optics.org

FOUNDING PUBLISHER Andreas Thoss, Berlin, Germany, Email: th@thoss-media.com

RESPONSIBLE FOR ADVERTISEMENTS Panagiota Herbrand, De Gruyter, Mies-van-der-Rohe-Straße 1, 80807 München, Germany.
Tel.: +49 (0)89 769 02 – 394, Fax: +49 (0)89 769 02 – 350
Email: panagiota.herbrand@degruyter.com

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